

Title (en)
SiC EPITAXIAL WAFER AND METHOD FOR MANUFACTURING SAME

Title (de)
EPITAKTISCHER SILICIUMCARBIDWAFER UND HERSTELLUNGSVERFAHREN DAFÜR

Title (fr)
GALETTE ÉPITAXIALE SiC ET SON PROCÉDÉ DE FABRICATION

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Application
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Abstract (en)
According to the present invention, there is provided an SiC epitaxial wafer which reduces triangular defects and stacking faults, which is highly uniform in carrier concentration and film thickness, and which is free of step bunching, and its method of manufacture. The SiC epitaxial wafer of the present invention is an SiC epitaxial wafer in which an SiC epitaxial layer is formed on a 4H-SiC single crystal substrate that is tilted at an off angle of 0.4°-5°, wherein the density of triangular-shaped defects of said SiC epitaxial layer is 1 defect/cm² or less.

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